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(71) Applicant: TOYODA GOSEI CO LTD

(72) Inventor:
KOIKE MASAYOSHI
MANABE KATSUhide
SHIBATA NAOKI
KATO HISAYOSHI
SASA MICHINARI
ASAI MAKOTO
YAMAZAKI SHIRO

(54) GROUP III NITRIDE SEMICONDUCTOR
LIGHT-EMITTING ELEMENT

constant in each layer may accord with the lattice
constant of the layer 3.

(57) Abstract:

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PROBLEM TO BE SOLVED: To improve luminous intensity and improve the turning blue of luminescent color.

SOLUTION: A buffer layer 2 of AlN 500 Å is formed on a sapphire board 1, and thereon a high carrier concentration n^+ layer 3 of silicon-doped GaN about 2.0 μm in thickness and $2 \times 10^{18}/\text{cm}^3$ in concentration of electrons, a high carrier concentration n^+ layer 4 of silicon-doped $(\text{Al}_{x2}\text{Ga}_{1-x2})_2\text{In}_{1-y2}\text{N}$ about 2.0 μm in thickness and $2 \times 10^{18}/\text{cm}^3$ in electron concentration, an n layer (luminous layer) 5 of zinc and silicon-doped $(\text{Al}_{x1}\text{Ga}_{1-x1})_2\text{In}_{1-y1}\text{N}$ about 2.0 μm in thickness, a p layer 6 of magnesium-doped $(\text{Al}_{x2}\text{Ga}_{1-x2})_2\text{In}_{1-y2}\text{N}$ about 1.0 μm in thickness and $2 \times 10^{17}/\text{cm}^3$ in hole concentration are formed in the order. An electrode 7 and an electrode 8 made of nickel are formed at the p layer 6 and a high concentration n^+ layer, respectively, and they are electrically isolated from each other by trench 9. The component ratios of Al, Ga, and In in the layers 4, 5, and 6 are selected, so that the lattice

